

FORM PTO-1449 (REV. 7-80)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO.: 423.1036		SERIAL NO.: To Be Assigned	
<b>LIST OF PRIOR ART CITED BY APPLICANT</b> (Use several sheets if necessary)				APPLICANT(S): JooHyeon PARK, et al.			
				FILING DATE: Herewith		GROUP: To Be Assigned	

J09711 U.S. PTO  
 10/07/02  
 02/11/02

U.S. PATENT DOCUMENTS											
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE				
	AA										
	AB										
	AC										
	AD										
	AE										
	AF										
	AG										

FOREIGN PATENT DOCUMENTS									
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION		
							YES	NO	
	AL								
	AM								
	AN								
	AO								
	AP								

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
S.J.L. ↓	AR	Robert D. Allen, et al., "Protecting Groups for 193-nm Photoresists", SPIE Vol. 2724 pp. 334-343.
	AS	Thomas I. Wallow, et al., "Evaluation of Cycloolefin-Maleic Anhydride Alternating Copolymers as Single-Layer Photoresists for 193 nm Photolithography", SPIE Vol. 2724, pp. 355-364.
	AT	
	AU	
	AV	

EXAMINER <i>Sim J. Lee</i>	DATE CONSIDERED <i>Sept. 7, 2003</i>
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.